



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
(213.003-D2-US)

In re Application of: **Ye et al.**

Serial No: **10/763,142**

Filed: **January 22, 2004**

Title: **Method and Apparatus for Monitoring
Integrated Circuit Fabrication**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

) Group Art Unit: **2125**

) Examiner:

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on May 4, 2004
Date

Michiko Siter
(person signing this certificate)

Michiko Siter
Signature

FIRST INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Submitted herewith are ten (10) sheets of a modified Form PTO-1449. All of the documents listed on the modified Form PTO-1449 were provided or cited in the parent application of the above-captioned application. Accordingly, the documents are not enclosed herewith. (See 37 C.F.R. §1.98(d) and MPEP 609). Should the Examiner desire an additional copy of the documents, kindly contact the undersigned.

It is respectfully requested that the Examiner make his/her consideration of these references formally of record with the initial Office Action.

Respectfully submitted,

Date: May 4, 2004

Neil A. Steinberg
Reg. No. 34,735
650-968-8079



U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 213.003-D2-US	SERIAL NUMBER 10/763,142
	APPLICANT(S) Ye et al.	
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